

**PATENT APPLICATION**  
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q79837

Ken MIYAGI, *et al.*

Continuation of Appln. No.: 09/793,958

Parent Group Art Unit: 1752

Parent Confirmation No.: 2382

Parent Examiner: John S. CHU

Parent Filing Date: February 27, 2001

For: PHENOL NOVOLAK RESIN, PRODUCTION PROCESS THEREOF, AND POSITIVE  
PHOTORESIST COMPOSITION USING THE SAME

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Prior to examination, please amend the above-identified application as follows on the  
accompanying pages.

**TABLE OF CONTENTS**

AMENDMENTS TO THE SPECIFICATION.....	2
AMENDMENTS TO THE CLAIMS .....	3
REMARKS .....	7